

## Electronic Acknowledgement Receipt

<b>EFS ID:</b>	2013784
<b>Application Number:</b>	10523492
<b>International Application Number:</b>	
<b>Confirmation Number:</b>	1866
<b>Title of Invention:</b>	Photoresists, fluoropolymers and processes for 157 nm microlithography
<b>First Named Inventor/Applicant Name:</b>	Andrew E. Feiring
<b>Correspondence Address:</b>	Jessica M Sinnott E I du Pont de Nemours and Company Legal - Patents 4417 Lancaster Pike Wilmington DE 19898 US - -
<b>Filer:</b>	Lois A. Santopietro/Diane Dick
<b>Filer Authorized By:</b>	Lois A. Santopietro
<b>Attorney Docket Number:</b>	SR0020USPCT
<b>Receipt Date:</b>	26-JUL-2007
<b>Filing Date:</b>	03-FEB-2005
<b>Time Stamp:</b>	12:52:05
<b>Application Type:</b>	U.S. National Stage under 35 USC 371

### Payment information:

Submitted with Payment	yes
Payment was successfully received in RAM	\$1020
RAM confirmation Number	7771

